

## REMARKS

### Summary of Claim Status

Claims 1-10 are pending in the present application after entry of the present amendment. Claims 1-7 are rejected for the reasons discussed below. Claims 8-10 are allowed. Applicant thanks the Examiner for this acknowledgement of patentable subject matter.

Applicant respectfully requests favorable reconsideration of the claims and withdrawal of the pending rejections in view of the present amendment and in light of the following discussion.

### Rejections Under 35 U.S.C. § 102

Claims 1-2 and 4-7 are rejected under 35 U.S.C. § 102(b) as being anticipated by Hayashi et al., U.S. Patent No. 4,980,308 ("Hayashi"). Applicant respectfully disagrees, traverses the rejection with respect to all claims, and submits that Hayashi does not teach or even suggest the claimed inventions. However, the present amendment to Claim 1 has rendered the rejection moot.

In particular, Applicant has amended Claim 1 to recite that at least one surface of the island substantially normal to the back side surface of the interconnect portion is exposed. Applicant respectfully submits that Hayashi does not teach or even suggest such a feature. As shown in Figs. 2A and 2B of Hayashi, no surface normal to a back side is exposed. For instance, the normal surfaces of source/drain regions 35sa, 35da, 35sb, and 35db of Hayashi are covered at all times by an insulating layer 52. At no time during the process described in Hayashi are those normal surfaces ever exposed. The insulating layer 52 is necessary both for acting as a mask for ion implantation processes (see, e.g., Hayashi at col. 4, lines 18-35), and for separating the p-MIS and the n-MIS (see, e.g., Hayashi at col. 5, lines 7-8). The source and drain regions of Hayashi are further covered by an insulating layer 4 and a wiring layer 6. Thus, it is clear that Hayashi does not teach or suggest a normal surface that is exposed.

In contrast, Claim 1, as amended, recites that at least one surface of the island substantially normal to the back side surface of the interconnect portion is exposed. For example, as shown in FIGs. 15 and 16 of the present application and as described in the corresponding text, an etching step may remove material, which leaves behind an island that has an exposed surface substantially normal to the back side.

Therefore, Applicant believes that the amendment to Claim 1 places the claim in form for allowance. Applicant respectfully requests entry of the amendment and allowance of the claim.

Claims 2 and 4-7 depend from Claim 1 and thus include all of the limitations of Claim 1. Applicant believes Claim 1 is allowable for the reasons set forth above. Therefore, for at least the same reasons, Applicant believes Claims 2 and 4-7 are also allowable, and respectfully requests allowance of such claims.

All of the above amendments are fully supported by the specification, for example in FIGs. 15 and 16 and the corresponding text.

#### Rejections Under 35 U.S.C. § 103

Claim 3 is rejected under 35 U.S.C. § 103(a) as being unpatentable over Hayashi in view of Matsumoto et al., U.S. Patent No. 6,794,717 ("Matsumoto"). Applicant respectfully disagrees and traverses the rejection. Applicant submits that Hayashi and Matsumoto, alone or in any combination, do not teach or suggest the present invention. Applicant believes, however, that the rejection is moot in light of the amendment to Claim 1. In particular, Applicant believes Claim 3 is allowable for at least the same reasons Claim 1 is believed allowable, and allowance of Claim 3 is therefore respectfully requested.

Conclusion

Applicant respectfully requests that the Examiner reconsider the final rejection and consider the above amendment and arguments. The amendment and the supporting arguments are believed to place the application in form for allowance. Therefore, Applicant respectfully requests allowance of the application. If any action other than allowance is contemplated by the Examiner, the Examiner is invited to telephone Applicant's attorney at 408-879-4641.

Respectfully submitted,



Justin Liu  
Attorney for Applicant  
Reg. No. 51,959

I hereby certify that this correspondence is being deposited with the United States Postal Service as first-class mail in an envelope addressed to: Commissioner for Patents, P.O. BOX 1450, Alexandria, VA 22313-1450, on November 29, 2005.

Julie Matthews  
Name

  
Signature